

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	2290	bellows and chamber and exposure	USPAT; US-PGPUB
2	BRS	L2	117	1 and (wafer adj chamber)	USPAT; US-PGPUB
3	BRS	L3	117	2 and vacuum	USPAT; US-PGPUB
4	BRS	L4	106	3 and @ad<20010425	USPAT; US-PGPUB
5	BRS	L5	95	4 and seal	USPAT; US-PGPUB

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	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
1	BRS	L1	5052	exposure and environment and (mask reticle) and (wafer substrate)	USPA T	2002/09/10 15:09	
2	BRS	L2	37	1 and (exposure adj apparatus) and (chamber same stage)	USPA T	2002/09/10 15:11	
3	BRS	L3	23	2 and seal\$3	USPA T	2002/09/10 15:11	
4	BRS	L4	19	3 and scan\$5	USPA T	2002/09/10 15:12	

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